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L	Hits	Search Text	DB	Time stamp
Number	1038	(/thormals2 adi2 /ovidation or ovidizing	HCDAT.	2004/05/26
1	1038	((thermal\$2 adj2 (oxidation or oxidizing or oxidized)) adj3 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:13
2	101	(("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and	USPAT; US-PGPUB; EPO; JPO;	2004/05/26 11:22
3	0	(@ad<20011012 or @rlad<20011012) (((thermal\$2 adj2 (oxidation or oxidizing or oxidized)) adj3 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012))) and ((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:14
4	0	(@ad<20011012 or @rlad<20011012)) ((thermal\$2 adj (oxidation or oxidizing or oxidized) adj in adj2 (cvd or (chemical adj vapor adj deposition)) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:15
5	28	((thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition) with chamber with in) and (@ad<20011012 or @rlad<20011012))) and ((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:18
6	19		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
7	0	<pre>((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012)) and (form\$3 with thermal\$3 with oxide with in with cvd with (furnace or chamber))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26
8	17	I	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
_	355	(gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2004/01/08 15:52
-	197	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	149	(((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/\$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	119	((((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/\$3.ccls.) and (gate with electrode)	USPAT; EPO; JPO; DERWENT	2002/07/30 13:55
-	145	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/31 15:55
-	76	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02

	59	(((gate with oxide) same (oxidiz\$3 with	USPAT;	2002/07/30
i		substrate) and (nitrid\$5 with (no or	EPO; JPO;	14:02
		(nitric with oxide))) and cvd) and	DERWENT	i i
		temperature and (atm or atmosphere or		
		torr)) and 438/\$3.ccls.		
-	5	(gate with oxide) same (oxidiz\$3 with	USPAT;	2002/07/30
		substrate) and ((nitrid\$5 with (no or	EPO; JPO;	15:11
		(nitric with oxide)) same boron)) and cvd	DERWENT	+
_	17	"5650344"	USPAT;	2002/07/30
			EPO; JPO;	15:11
			DERWENT	
_	14	"5403786"	USPAT;	2002/07/31
			EPO; JPO;	14:16
			DERWENT	
_	26	(gate with oxide) same (oxidiz\$3 with	USPAT;	2002/07/31
		substrate) and (nitrid\$5 with (no or	EPO; JPO;	15:57
		(nitric with oxide))) and cvd and ono and	DERWENT	10.01
		(gate adj electrode)	DEIWENT	
_	22	(gate with oxide) same (oxidiz\$3 with	USPAT;	2002/07/31
1 -	22	substrate) and (nitrid\$5 with (no or	EPO; JPO;	16:33
		(nitric with oxide))) and cvd and ono and	DERWENT	10.33
		((gate adj electrode) with (silicon or	TATALITE	
	1 1 1	polysilicon))	IICDAT.	2002/07/31
-	11	((gate with oxide) same (oxidiz\$3 with	USPAT;	15:58
		substrate) and (nitrid\$5 with (no or	EPO; JPO;	12:20
		(nitric with oxide))) and cvd and one and	DERWENT	
		((gate adj electrode) with (silicon or		
		polysilicon))) and tungsten	TICDAM:	2002/07/21
-	3	(gate with oxide) same (oxidiz\$3 with	USPAT;	2002/07/31
		substrate) and (nitrid\$5 with (no or	EPO; JPO;	16:56
		(nitric with oxide))) and cvd and ono and	DERWENT	
		(((gate adj electrode) with polycide)		
		same tungsten)		1 2002 (07 (21
-	17	"5650344"	USPAT;	2002/07/31
			EPO; JPO;	16:56
	ŀ		DERWENT	(-1 (1)
-	3554	(nitrid\$5 with gate with oxide) and cvd	USPAT;	2003/01/13
			EPO; JPO;	12:32
			DERWENT	
-	0		USPAT;	2003/01/13
		(nitirc adj oxide)) and cvd	EPO; JPO;	12:33
			DERWENT	
-	5		USPAT;	2003/01/13
		(nitric adj oxide)) and cvd	EPO; JPO;	12:33
		L., ., ., ., .,	DERWENT	0000/07/70
-	6		USPAT;	2003/01/13
		(nitric adj oxide)) and cvd	US-PGPUB;	14:55
			EPO; JPO;	
			DERWENT	
-	0	11040681.URPN.	USPAT	2003/01/13
			l	14:46
-	2	5726087.pn.	USPAT;	2003/01/13
			US-PGPUB;	16:28
			EPO; JPO;	
			DERWENT	
-	355	dry adj oxide	USPAT;	2003/01/13
1			US-PGPUB;	16:49
			EPO; JPO;	
			DERWENT	/ /
1 -	518	(gate adj oxide) with angstrom with ("10"	USPAT;	2003/01/13
		or "15" or "20")	US-PGPUB;	16:51
			EPO; JPO;	
	1		DERWENT	
-	341	(gate adj oxide) with angstrom with ("10"	USPAT;	2003/01/13
		or "15")	US-PGPUB;	17:23
			EPO; JPO;	
			DERWENT	
-	234		USPAT;	2003/01/13
] .	("10" or "15")) and nitrid\$5	US-PGPUB;	17:06
			EPO; JPO;	
	<u> </u>		DERWENT	

-	46	((gate adj oxide) with angstrom with	USPAT;	2003/01/13
1		("10" or "15")) same nitrid\$5	US-PGPUB;	17:06
i			EPO; JPO;	
			DERWENT	
_	8	(gate adj oxide) with angstrom with ("10"	USPAT;	2003/01/13
		or "15") with (ultra near2 thin)	US-PGPUB;	17:24
l		Of 13) with (ditta hearz thin)	1	17.24
ļ			EPO; JPO;	
			DERWENT	
-	121	(no or (nitric with oxide)) and cvd and	USPAT;	2004/01/08
		(nitrogen with dop\$3 with oxide) and	US-PGPUB;	15:58
		(thermal adj oxidation)	EPO; JPO;	
		(,	DERWENT	
_	108	((no or (nitric with oxide)) and cvd and	USPAT;	2004/01/08
	100			,
		(nitrogen with dop\$3 with oxide) and	US-PGPUB;	15:59
		(thermal adj oxidation)) and	EPO; JPO;	
i		(@ad<20011012 or @rlad<20011012)	DERWENT	
-	100	("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
		cvd and (nitrogen with dop\$3 with oxide)	US-PGPUB;	18:14
		and (thermal adj oxidation)	EPO; JPO;	
		dira (direction)	DERWENT	
	0.0	//!mail/a /mibuit	1	2004/01/09
-	93	(("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
		cvd and (nitrogen with dop\$3 with oxide)	US-PGPUB;	18:15
		and (thermal adj oxidation)) and	EPO; JPO;	ļ l
		(@ad<20011012 or @rlad<20011012)	DERWENT	
_	88	("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
		cvd and ((thermal adj oxidation) same	US-PGPUB;	18:15
		(thermal adj nitridation))	EPO; JPO;	
		(thermal adj hitridation))		
			DERWENT	
-	85	(("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
		cvd and ((thermal adj oxidation) same	US-PGPUB;	18:32
	•	(thermal adj nitridation))) and	EPO; JPO;	
 		(@ad<20011012 or @rlad<20011012)	DERWENT	[
l _	2	("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
	-	cvd and ((thermal adj oxidation) same	US-PGPUB;	18:32
i				10:32
		(thermal adj nitridation) same (gate adj	EPO; JPO;	į į
		oxide))	DERWENT	
-	31	("no".u/c. or (nitric with oxide)) and	USPAT;	2004/01/08
		cvd and ((thermal adj oxidation) same	US-PGPUB;	18:32
		(gate adj oxide)) and (thermal adj	EPO; JPO;	
		nitridation)	DERWENT	
_	30	(("no".u/c. or (nitric with oxide)) and	USPAT;	2004/05/19
] 30		US-PGPUB;	16:27
		cvd and ((thermal adj oxidation) same		1 10.27
		(gate adj oxide)) and (thermal adj	EPO; JPO;	
		nitridation)) and (@ad<20011012 or	DERWENT	
		@rlad<20011012)		
-	580	("no".u/c. or (nitric with oxide)) and	USPAT;	2004/05/19
		cvd and (thermal\$2 with oxidation) and	US-PGPUB;	16:30
		(nitriding or nitridation) and	EPO; JPO;	
		temperature and pressure and	DERWENT	
			DEVARIAT	
		(@ad<20011012 or @rlad<20011012)		1 2224 (25 /22
-	16	(("no".u/c. or (nitric with oxide)) same	USPAT;	2004/05/19
		(nitriding or nitridation) same	US-PGPUB;	17:00
		temperature and pressure) and (thermal\$2	EPO; JPO;	
		same (oxidation or oxidizing or oxidized)	DERWENT	
		same temperature same pressure) and cvd	1	
		and (@ad<20011012 or @rlad<20011012)		1
I _	246		USPAT;	2004/05/19
	246	(thermal\$2 with (oxidation or oxidizing		
		or oxidized) with (cvd or (chemical adj	US-PGPUB;	16:59
		vapor adj deposition)) same temperature	EPO; JPO;	
		same pressure) and (@ad<20011012 or	DERWENT	
		@rlad<20011012)]
-	10	(("no".u/c. or (nitric with oxide)) same	USPAT;	2004/05/19
	19	(nitriding or nitridation) same	US-PGPUB;	17:04
[EPO; JPO;	- / · · ·
		temperature same pressure same (cvd or		l i
-		(chemical adj vapor adj deposition))) and	DERWENT	
		(@ad<20011012 or @rlad<20011012)	L	

			·	
-] 1	((thermal\$2 with (oxidation or oxidizing	USPAT;	2004/05/25
		or oxidized) with (cvd or (chemical adj	US-PGPUB;	18:24
		vapor adj deposition)) same temperature	EPO; JPO;	
		same pressure) and (@ad<20011012 or	DERWENT	
		@rlad<20011012)) and ((("no".u/c. or		
		(nitric with oxide)) same (nitriding or		
		nitridation) same temperature same		
		pressure same (cvd or (chemical adj vapor		
		adj deposition))) and (@ad<20011012 or		
		@rlad<20011012))		
-	101	(("no".u/c. or (nitric with oxide)) same	USPAT;	2004/05/26
		temperature same pressure same (cvd or	US-PGPUB;	11:14
		(chemical adj vapor adj deposition))) and	EPO; JPO;	
		(@ad<20011012 or @rlad<20011012)	DERWENT	
_	8	((thermal\$2 with (oxidation or oxidizing	USPAT;	2004/05/19
		or oxidized) with (cvd or (chemical adj	US-PGPUB;	17:04
		vapor adj deposition)) same temperature	EPO; JPO;	
		same pressure) and (@ad<20011012 or	DERWENT	
		@rlad<20011012)) and ((("no".u/c. or		
	İ	(nitric with oxide)) same temperature		
		same pressure same (cvd or (chemical adj		
		vapor adj deposition))) and (@ad<20011012		
		or @rlad<20011012))		
_	19	(("no".u/c. or (nitric with oxide)) same	USPAT;	2004/05/20
	19	temperature same (gate with (oxide or	US-PGPUB;	07:19
		dielectric)) same pressure same (cvd or	EPO; JPO;	` ' · · · ·
			DERWENT	
		(chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012)	DEKMENI	
	_		HCDAT.	2004/05/20
⁻	6	(("no".u/c. or (nitric with oxide)) with	USPAT;	07:29
		(cvd or (chemical adj vapor adj	US-PGPUB;	07:29
		deposition)) with in with (nitriding or	EPO; JPO;	
		nitridation)) and (@ad<20011012 or	DERWENT	į į
		@rlad<20011012)	Hansa.	3004/05/30
-	30	(("no".u/c. or (nitric with oxide)) with	USPAT;	2004/05/20
		(cvd or (chemical adj vapor adj	US-PGPUB;	07:49
		deposition)) with in) and (@ad<20011012	EPO; JPO;	
		or @rlad<20011012)	DERWENT	0004/05/00
-	0	((("no".u/c. or (nitric with oxide)) with	USPAT;	2004/05/20
		(cvd or (chemical adj vapor adj	US-PGPUB;	07:29
		deposition)) with in with (nitriding or	EPO; JPO;	
		nitridation)) and (@ad<20011012 or	DERWENT	
		@rlad<20011012)) not ((("no".u/c. or		
		(nitric with oxide)) with (cvd or		
		(chemical adj vapor adj deposition)) with		
		in) and (@ad<20011012 or @rlad<20011012))		1 2004 (05 (22
-	24	((("no".u/c. or (nitric with oxide)) with		2004/05/20
		(cvd or (chemical adj vapor adj	US-PGPUB;	07:30
		deposition)) with in) and (@ad<20011012	EPO; JPO;	
		or @rlad<20011012)) not ((("no".u/c. or	DERWENT	
		(nitric with oxide)) with (cvd or		
		(chemical adj vapor adj deposition)) with		
		in with (nitriding or nitridation)) and		
		(@ad<20011012 or @rlad<20011012))		
[-	6	(("no".u/c. or (nitric with oxide)) with	USPAT;	2004/05/25
		(cvd or (chemical adj vapor adj	US-PGPUB;	18:26
		deposition)) with furnace) and	EPO; JPO;	
		(@ad<20011012 or @rlad<20011012)	DERWENT	
-	4134	(thermal\$2 with (oxidation or oxidizing	USPAT;	2004/05/25
		or oxidized) with (cvd or (chemical adj	US-PGPUB;	18:53
		vapor adj deposition) with chamber with	EPO; JPO;	
		in) and (@ad<20011012 or @rlad<20011012))	DERWENT	
-	266	(("no".u/c. or (nitric with oxide)) with	USPAT;	2004/05/25
		(cvd or (chemical adj vapor adj	US-PGPUB;	18:27
		deposition))) and (@ad<20011012 or	EPO; JPO;	
	<u> </u>	@rlad<20011012)	DERWENT	<u> </u>
				· · · · · · · · · · · · · · · · · · ·

	13	(((thermal\$2 with (oxidation or oxidizing	USPAT;	2004/05/25
-	13	or oxidized) with (cvd or (chemical adj	US-PGPUB;	18:27
		vapor adj deposition) with chamber with	EPO; JPO;	10:27
		in) and (@ad<20011012 or	DERWENT	
		@rlad<20011012))) and ((("no".u/c. or		
		(nitric with oxide)) with (cvd or		
		(chemical adj vapor adj deposition))) and		
	i	(@ad<20011012 or @rlad<20011012))) and		
	1	temperature and pressure		
-	1038		USPAT;	2004/05/26
		or oxidized) adj3 (cvd or (chemical adj	US-PGPUB;	11:13
		vapor adj deposition) adj2 chamber) and	EPO; JPO;	
		(@ad<20011012 or @rlad<20011012))	DERWENT	
_	0		USPAT;	2004/05/25
		oxidized) adj in adj2 (cvd or (chemical	US-PGPUB;	18:58
		adj vapor adj deposition) adj chamber)	EPO; JPO;	
		and (@ad<20011012 or @rlad<20011012))	DERWENT	
_	0	I	USPAT;	2004/05/25
		or oxidized) adj2 in adj2 (cvd or	US-PGPUB;	18:54
		(chemical adj vapor adj deposition) adj2	EPO; JPO;	
		chamber) and (@ad<20011012 or	DERWENT	
		@rlad<20011012))		
_	1 0	-	USPAT;	2004/05/25
		or oxidized) adj3 in adj3 (cvd or	US-PGPUB;	18:58
		(chemical adj vapor adj deposition) adj3	EPO; JPO;	
		chamber) and (@ad<20011012 or	DERWENT	
		@rlad<20011012))		
_	1 0	-	USPAT;	2004/05/25
		or (chemical adj vapor adj deposition)	US-PGPUB;	18:57
		adj chamber) and (@ad<20011012 or	EPO; JPO;	
		@rlad<20011012))	DERWENT	
_	543		USPAT;	2004/05/25
	343	(chemical adj vapor adj deposition) adj	US-PGPUB;	18:57
		chamber) and (@ad<20011012 or	EPO; JPO;	
		@rlad<20011012))	DERWENT	
_	0	-	USPAT;	2004/05/26
		or oxidized) adj in adj2 (cvd or	US-PGPUB;	11:15
		(chemical adj vapor adj deposition)) adj	EPO; JPO;	
		chamber) and (@ad<20011012 or	DERWENT]
		Criamber/ and (ead\20011012 01	DUINNUIT	
_		((thermal\$2 adj3 (oxidation or oxidizing	USPAT;	2004/05/25
_		or oxidized) adj3 in adj3 (cvd or	US-PGPUB;	18:59
		(chemical adj vapor adj deposition)) adj3	EPO; JPO;	10.00
		chamber) and (@ad<20011012 or	DERWENT	
	1	Chamber and (ead<20011012 01 @rlad<20011012 01	DUMBIAT	